



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

2814

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Applicant: Nobutoshi AOKI Attorney Docket 40301/0578

Title: SEMICONDUCTOR INTEGRATED CIRCUIT INCLUDING
INSULATED GATE FIELD EFFECT TRANSISTOR AND METHOD
OF MANUFACTURING THE SAME

Appl. No.: 09/440,928

Filing Date: November 16, 1999

Examiner: S. Rao

Art Unit: 2814

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TECHNOLOGY CENTER 2800TRANSMITTALCommissioner for Patents
Washington, D.C. 20231

Sir:

Transmitted herewith is a Preliminary Amendment in the above-captioned application. The fee has been calculated as shown below. *(Small entity fees indicated in parentheses.)*

CLAIMS AS AMENDED						
(1)	(2)	(3)	(4)	(5)	(6)	(7)
	Claims Remaining After Amendment		Highest Number Previously Paid For	Extra Claims	Rate	Fee
Total Claims	31	-	27	4	18.00	\$72.00
<i>(Small Entity)</i>					<i>(9.00)</i>	
Independent claims	10	-	9	1	84.00	\$84.00
<i>(Small Entity)</i>					<i>(42.00)</i>	
Multiple Dependent		-			280.00	
<i>(Small Entity)</i>					<i>(140.00)</i>	
Extension of Time	One Month		Two Months	Three Months	Four Months	
Fee	\$110		\$400	\$920	\$1,440	
<i>(Small Entity)</i>	<i>(\$55)</i>		<i>(\$200)</i>	<i>(\$460)</i>	<i>(\$720)</i>	
Total Fees						\$156.00

A check in the amount of the above Total Fees is attached. This amount is believed to be correct; however, the Commissioner is hereby authorized to charge any deficiency or credit any overpayment to Deposit Account No. 19-0741.

Respectfully submitted,

Aaron C. Chatterjee
Reg. No. 41,398

Date: February 26, 2002

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(202) 672-5300



Attorney Docket 040301-0578

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AMENDMENT AND RESPONSE UNDER 37 C.F.R. § 1.111

Commissioner for Patents
Washington, D.C. 20231

Sir:

In reply to the Office Action mailed November 26, 2001, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend the claims by replacing the indicated claims with the following clean versions. (See **Attachment A** for the marked up version of the amended claims.)

- ai Sub
B1
cont.
1. (Amended) A semiconductor device comprising:
a pair of main electrodes used as source and drain electrodes;
an insulating gate film adjacent to the pair of main electrodes; and
a gate electrode comprising of a first region composed at least a first group IV element and a second group IV element and formed in contact with the insulating gate film, and a second region composed of the first group IV element and formed on the first region.

03/04/2002 SSITHIB1 00000033 09440928

01 FC:102
02 FC:103

84.00 DP
72.00 DP